

GAMA Automated Wet Station

System Overview

The GAMA Series automated wet station is a flexible, modular system suitable for a wide variety of cleaning, etching and stripping applications for bare & reclaimed silicon wafers, IC devices, MEMS and photomasks.

Substrate Size:	150 mm, 200 mm, 300 mm
Applicable material:	Silicon, Glass
Technology Markets:	Analog IC, Power IC, MEMS, R&D

Processes

- Pre-Diffusion Clean
- Nitride Etch
- Photoresist Strip
- Post Ash/Etch Clean
- Advanced Front End of Line Clean
- Pre-Epitaxial Clean
- Cu Clean / Low-k
- Cobalt Silicide Clean
- Silicon Post Polish Clean
- Silicon Final Clean
- Surface/Bulk Micromachining
- Post DRIE Clean

Production Advantages

- Batch immersion process solution for all FEOL and BEOL semiconductor applications
- Can process 300 mm and 200 mm wafers concurrently
- Performance proven platform
- Modular design, highly flexible, customizable to meet any process flow and throughput requirement
- Concentration control and dilute chemistry for low cost of ownership
- Space saving, multi-process tool configurations
- Advanced megasonic cleaning technology
- Multiple lot / multiple recipe processing
- Full SECS GEM interface



GAMA Automated Batch Wet Immersion Station